PHOTOGRAPHS OF EQUIPMENTS/INSTRUMENTS

RF/DC Magnetron sputtering unit

(Hind High Vacuum Co. Pvt. Ltd., Bangalore; Model: BC 300)



Specifications:

SS 304 Vacuum chamber (400 mm (W) X 400 mm (D) X 500 mm (Ht)) Magnetron source: 03 Nos. of HHV make of 2" size DC Power supply: 2400 W DC Air cooled RF Power supply: M/s SEREN USA MAKE of 300 watts with auto matching network Mass flow controllers-2 Nos. of M/s. BRONKHORST Make Cooling system for chamber, magnetron and diffusion pump

Applications: Preparation of Metal,

Semiconductor, Ceramic nanostructured thin films, Nanocomposites and Nanomultilayers, Deposit thin films of various materials in integrated circuit processing, Semiconducting industry, metallisation, barrier layers, display circuitry, discrete components.

Spin Coater- Thin film deposition unit

(Spektrospin Spin coater)



Specifications:

Actuator: PID based speed controlled DC motor Spinning speed: 500-10,000 RPM Multistep RPM/Time programming Speed accuracy: ±0.1% Time Prog. 1-1200 secs. Acceleration: 1000-3000 rpm/sec. Gas purging facility Operation 230 V & 50 Hz Applications: Preparation of Metal oxides and polymer thin films

Dip Coater- Thin film deposition unit (Spektron model Dip coater)



Specifications:	
Dipping speed	1mm-250
mm/min	
Dipping length: 200 mm	
Dipping time: 60 min	
Drying delay: 60 min	
Voltage operation	n: 230 V & 50
Hz.	
Software an	d interface
electronics	

Applications: Preparation of Metal oxide thin films

Digital pH meter



UV-Visible spectrophotometer



Specifications:

Wavelength range : 190 nm-1100 nm Resolution : 1±0.2 nm Wavelength accuracy: ±0.1 nm Photometric system : Double bam optics Light source: 20 W halogen lamp, Deuterium lamp Detector: silicon photodiode Sample compartment: 110×250×115 mm (W×D×H)

Applications: Study of Optical properties of thin films and liquid samples

<u>Ultrasonic cleaner</u>



Probe Sonicator



<u>Muffle furnace 1000° C</u>



Vacuum oven





